

# PANDA MVD electronics developments in Torino

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INFN sez. di Torino

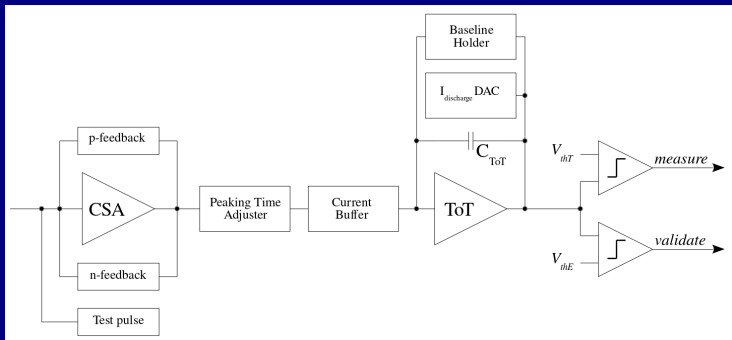
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# SSDs readout requirements

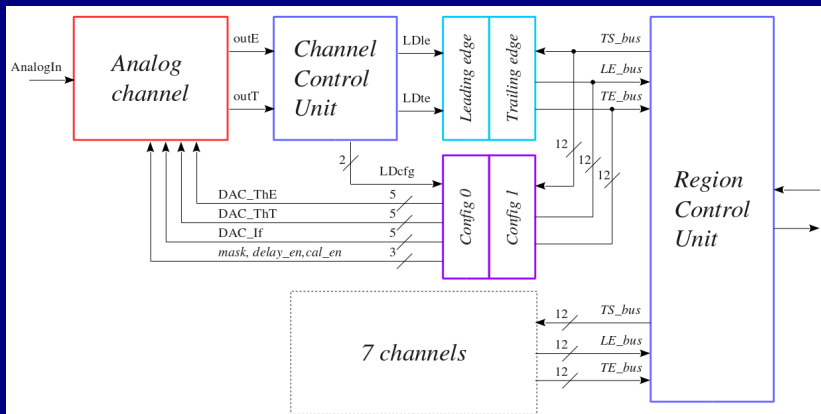
<b>Specification</b>	<b>Min</b>	<b>Max</b>	<b>Unit</b>
Channels per chip	64		
ToA (pk-pk)		6.25	ns
ToA (r.m.s.)		1.8	ns
Charge resolution	8		bits
Input charge	1	40	fC
Input capacitance	2	17	pF
Max rate per strip		40	kHz
Noise		1500	e <sup>-</sup>
Preamp peaking time	50	≥ 100	ns
Reference clock		160	MHz
Power consumption		256	mW
Radiation tolerance		20	kGy
Chip dimensions	4.5 × 3.5		mm <sup>2</sup>
Pads position	On two sides only		

# ToASt analog channel



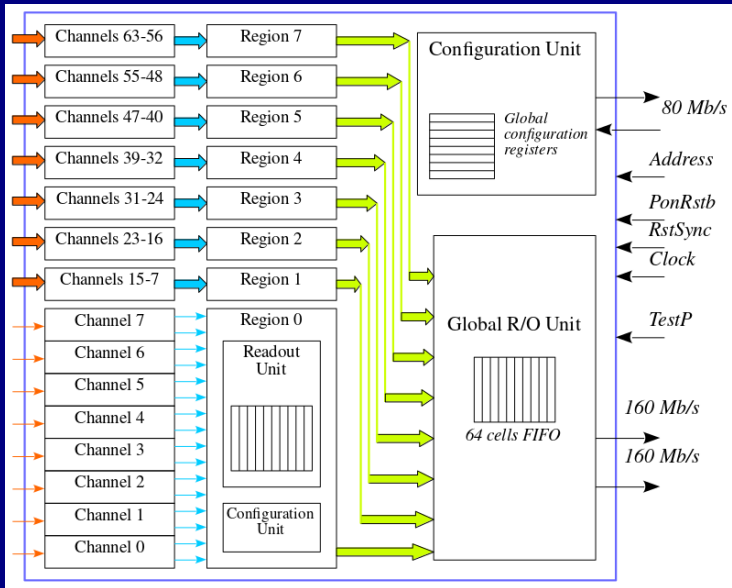
- CSA with selectable input signal polarity, gain  $\approx 5$  mV/fC
- Shaper with adjustable peaking time
- Current buffer
- Test pulse injection via integrated capacitor
- ToT stage with programmable discharge current
- Low frequency feedback to set baseline
- Two comparators with independent thresholds
- Local DACs for threshold and discharge current fine tuning

# ToASt channel schematic

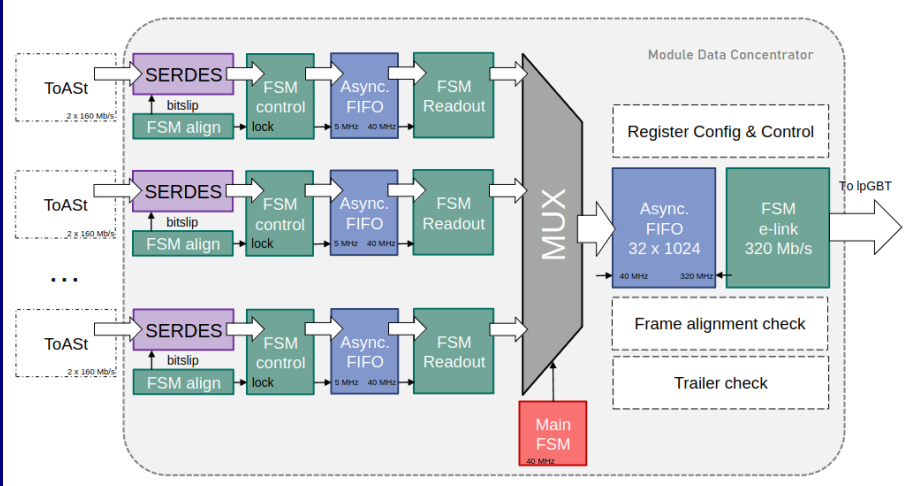


- Common time reference : 12 bits time stamp distributed to all channels
- Time stamp are Gray-encoded
- LE and TE registers latch time stamp at comparator rising/falling edges

# ToASt architecture

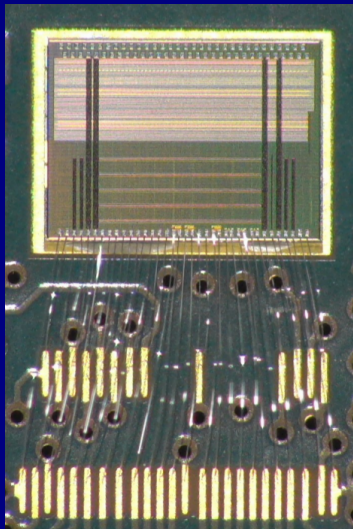


# Data concentrator



→ Details in M. Caselle presentation later in this session

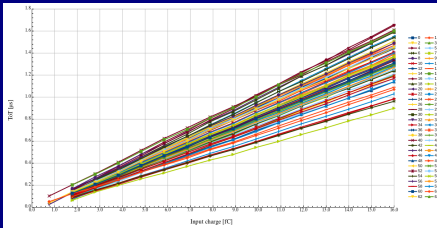
# ToASt version 1



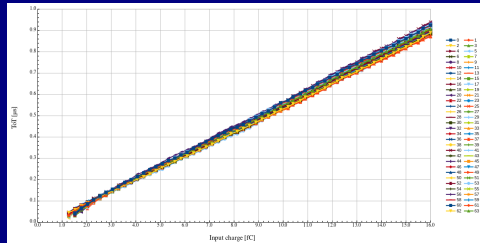
- CMOS 110 nm technology
- Digital-on-top design flow
- Die size :  $3.24 \times 4.41 \text{ mm}^2$
- Left pads pitch (on two rows) :  $63 \mu\text{m}$
- Right pads pitch :  $90 \mu\text{m}$
- Three power domains : analog, digital, digital pads (*all supply voltages at 1.2 V*)
- One external analog reference ( $V_{BG} = 600 \text{ mV}$ )
- SLVS driver/receivers
- TMR protected digital logic (*using CERN TMRG tool*)

# Measurement - transfer function

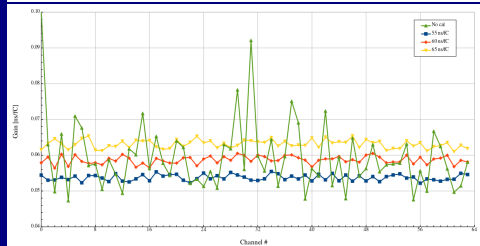
Before calibration



After calibration (gain & offset)

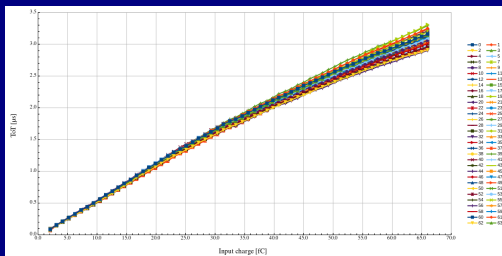
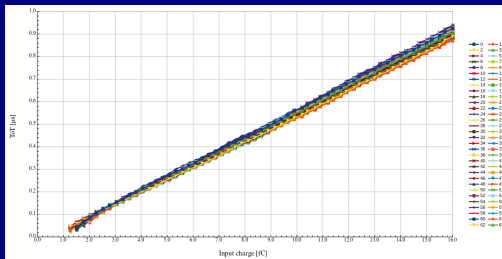


- Fully functional at 160 and 200 MHz
- Calibration reduces gain spread from 12% to 1.7% and offset spread reduced from 30% to 5.8%
- Power consumption : 180 mW @1.2 V



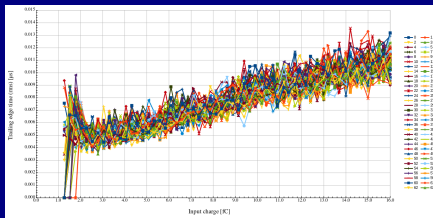
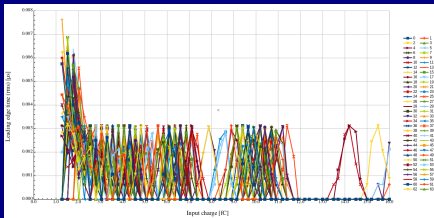
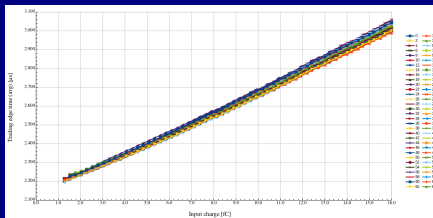
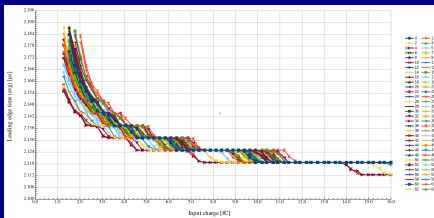


# Measurement - test pulse ranges



- Test pulse input with internally programmable amplitude via 6+1 bit internal DAC.
- Two test pulse ranges (*the +1 bit*):
  - Normal range : up to 16 fC, step 0.25 fC
  - Extended range : up to 66 fC, step 1.03 fC
- Non linearity (rms)  $< 0.64\%$  in the  $2 \div 16$  fC range

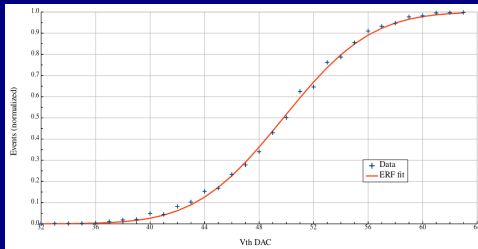
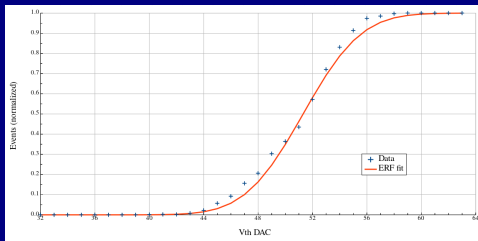
# Measurement - leading and trailing edge



- Test : test pulses synchronous with reset

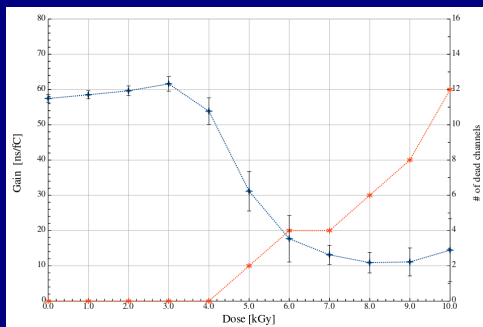
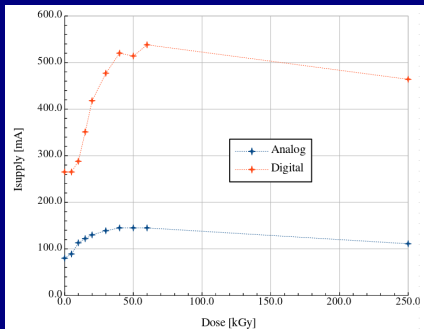
- Events per channel : 100
- Time bin : 6.25 ns

# Measurement - noise



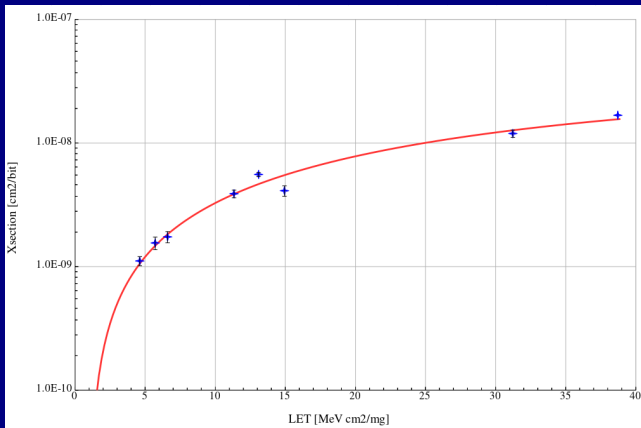
- S-curve obtained with channel threshold scan
  - Test pulse resolution and global threshold resolution too coarse
  - Baseline resolution gives similar results but with fewer points
- Conversion from DAC codes to input charge from simulations
- No input capacitance
- Average noise :  $0.034 \text{ fC}$  ( $211 \text{ e}^-$ )
- Maximum noise :  $0.05 \text{ fC}$  ( $312 \text{ e}^-$ )

# TID test (@ University of Padova)



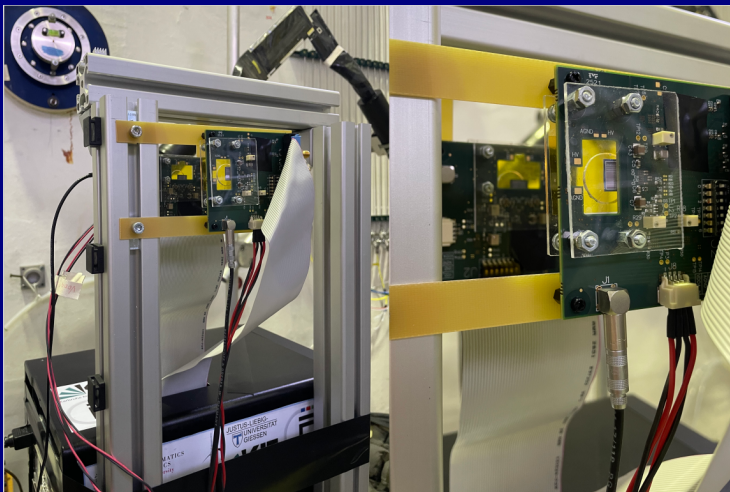
- Digital interface still working after 250 kGy
- Power consumption increase after 10 kGy (expected : leakage current in MOS)
- Gain drop after 4 kGy (unexpected)
- Full recovery after high T annealing
- Problem traced back to leakage current in analog switches
  - Enclosed layout has been adopted for switches in ToASt v2

# SEU test (@ INFN LNL SIRAD facility)



- Ion fluence  $\sim 5 \cdot 10^7$  per ion
- Estimated cross section for 200 MeV protons :  $3 \times 10^{-15}$  cm<sup>2</sup>
- Hadron flux  $5 \times 10^6$  hadrons/(cm<sup>2</sup> × s)  $\rightarrow 9.3 \times 10^{-2}$  errors/(h chip)
- Only 1→0 errors observed - triplication error found in the Verilog code

# Beam test at COSY - experimental set-up



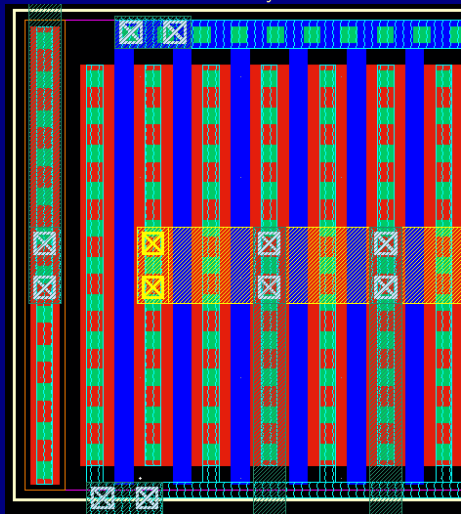
→ Details in H.G. Zaunick presentation later in this session

# Changes from v1 to v2 - 1

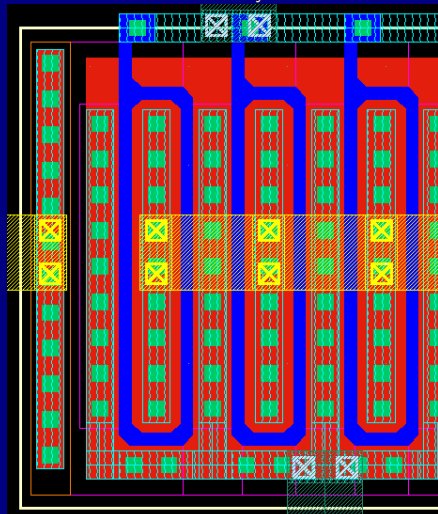
- Die size :  $3.24 \times 4.41 \text{ mm}^2 \rightarrow 3.24 \times 4.59 \text{ mm}^2$
- Same pinout as v1
- Reference voltage generated by internal bandgap
  - $V_{BG}$  pin still present for filtering
  - Internal bandgap can be disabled (GCR2[11])
- Enclosed layout for analog switches
  - It should solve the analog functionality issue
  - It will not solve the power supply increase issue
- Channel DACs threshold voltage resolution has been increased from 5 to 6 bits.
  - Range bits for these two DACs has been moved to CCR0[9:8].

# Enclosed layout

Standard layout

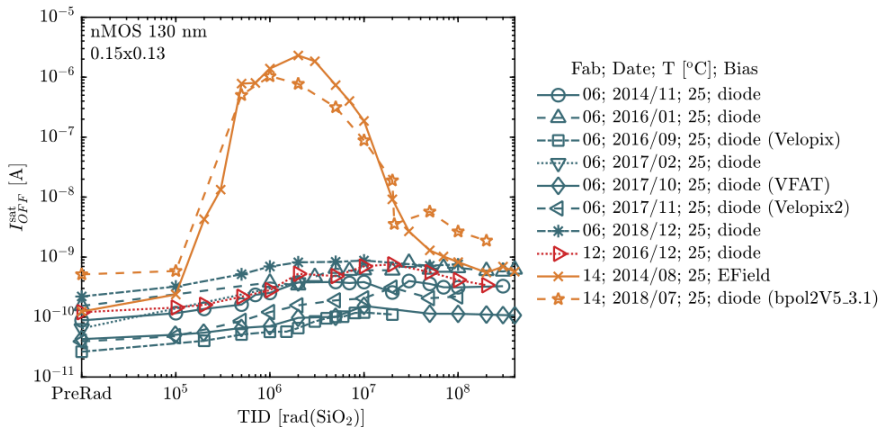


Enclosed layout





# Leakage current variability



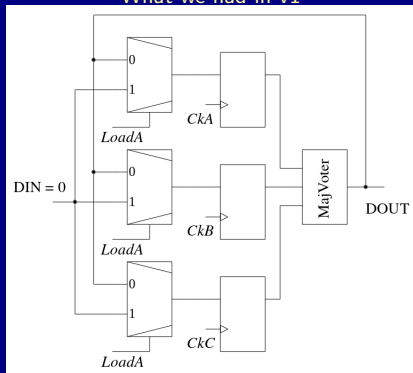
F.Faccio et al., Variability of the TID response of transistors in <omiss> 130nm technology

Note : We do not have data for our 110 nm technology.  
These are the closest ones I could find.

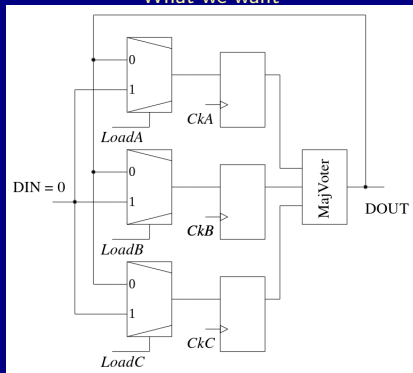
# Changes from v1 to v2 - 2

- Full review of the digital part
  - Change in synthesis tool to avoid TMR removal
  - Improvement in triplication structure
  - New TMR design guidelines from CERN

What we had in v1



What we want



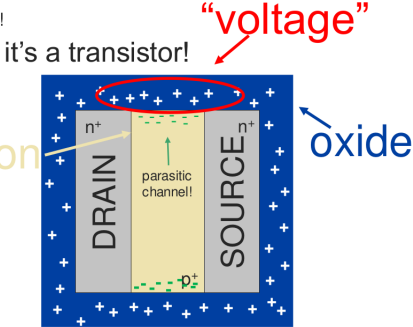
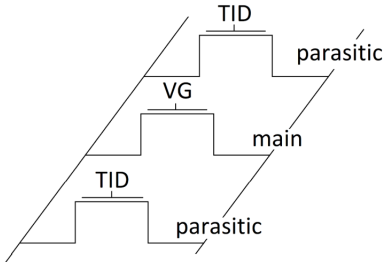
# Design status and plans

- ToASt v1 fully functional
  - Extensively tested in lab at 160 and 200 MHz
  - Beam test results very promising, work ongoing
  - Issues in radiation tolerance found, corrected in v2
- ToASt v2 submitted on February 26<sup>th</sup> 2024
  - delivery expected on August 5<sup>th</sup> 2024
- Same test board as v1
  - minor changes in the software are required
- Beam time requested to LNL in 4Q2024 for v2 SEU test

# Spare slides

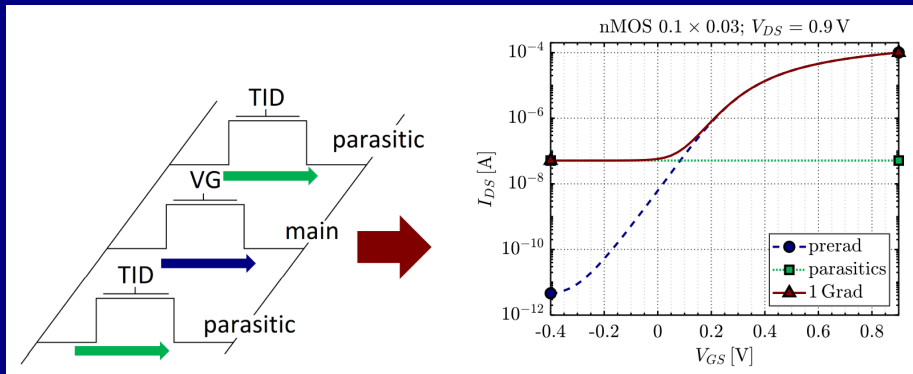
# MOS intrinsic parasitic transistor

positive charge attracts electrons -> **problem only in nMOS!**



G. Borghello, Radiation effects on 28nm CMOS technology

# Radiation induced leakage current



G. Borghello, Radiation effects on 28nm CMOS technology

Note :  $I_{DS}$  values are for a 28 nm technology.